

**IEEE SW Test Workshop** Semiconductor Wafer Test Workshop

> June 8, 2009 San Diego, CA

### A Challenge of 150k Probes on 300mm

Satoshi Sasaki <sasaki@aset.tokyoinfo.or.jp>

### Yoshiro Nakata

<nakata@aset.tokyoinfo.or.jp>



Chip Test Technology Research Lab.

Association of Super-Advanced Electronics Technologies (ASET)

This work is under NEDO entrustment project.

NEDO [The New Energy and Industrial Technology Development Organization] is Japan's largest public R&D management organization.

## Outline

1. What is ASET 2. Background 3. Target & issue 4. Probe detail 5. Countermeasure 6. Results & field data 7. Summary



## about ASET?

- Association of Super-Advanced Electronics Technologies (ASET) is a consortium making up with Japanese electronics companies.
- Established :1996
- Purpose:

Contribute to the enhancement of the competitiveness of Japanese industry and the establishment of an advanced information society.

• Activities:

Research and develop on industry-wide fundamental technologies in the semiconductor and other advanced electronics technology fields as well as practical applications of research results.

http://www.aset.or.jp/english/e-index.html



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Total 32



### Organization

**3D-Integration Technology Research Dept.** 

Design Environment Technology Lab. (Tokyo)

6 Companies

Chip Test Technology Lab. (Kawasaki, JAPAN)

ADVANTEST Panasonic SHARP TOKYO ELECTRON YAMAICHI ELECTRONICS

The Univ. of Tokyo Toyama Prefectural Univ.

> 5 Companies/ 2 University

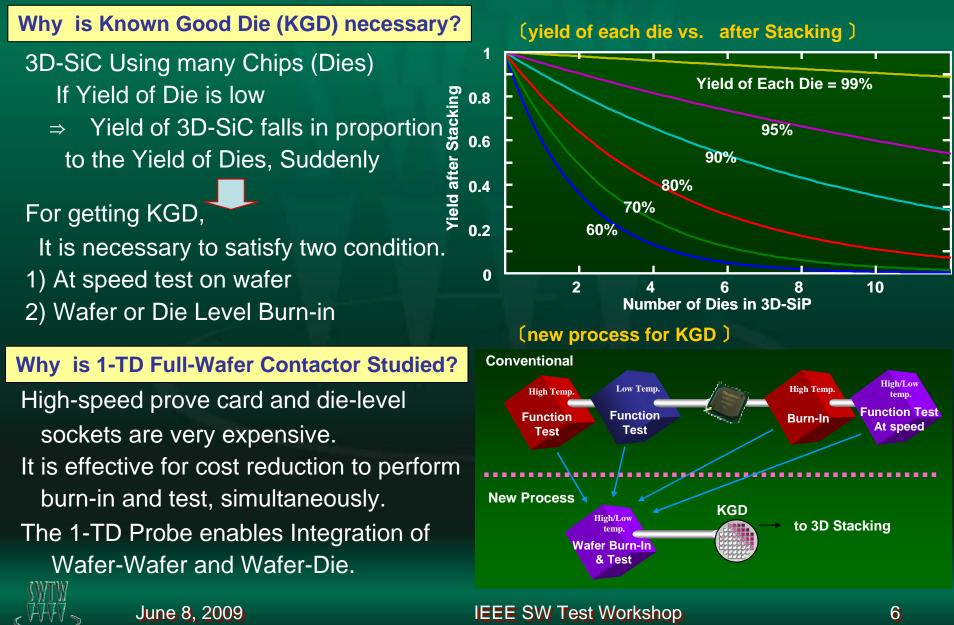
3D-Integration Basic Technology Lab. (Hachioji)

**11** Companies



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### Background



### **Study about Target Device**

#### The number of pads and Power per one wafer

Device Type	Number of	P/S and grand number/wafer	Signal numbers/wafer	Power	
SoC high end	500	VDD 256 ~ / chip GND 256 ~ / chip	I/O 512 ~ / chip	~ 10kA	
		Total 250,000 / wafer	Total 250,000 / wafer	~ 30kW	
SoC middle class	1000 ~ 2000	VDD 100 ~ / chip GND 100 ~ / chip	I/O 256 ~ 512 / chip	~ 5kA	
		Total 400,000 / wafer	Total 500,000 / wafer	~ 15kW	
SoC low end	3000 ~ 5000	VDD 50 ~ / chip GND 50 ~ / chip	I/O 256~ / chip	~ 5kA ~ 10kW	
		Total 500,000 / wafer	Total 750,000 / wafer		
DRAM	500 ~ 1500	VDD 25 ~ / chip GND 25 ~ / chip	Dr. 30 ~ / chip I/O 15 ~ / chip	~ 300A	
1		Total 75,000 / wafer	Total 68,000 /wafer	~ 400W	
Flash memory	500 ~ 1500	VDD 10~ / chip GND 10~ / chip	Dr. 10 ~ / chip I/O 10~ / chip	~ 100A	
		Total 30,000 / wafer	Total 60,000 /wafer	~ 200W	

Source : Prepared by Chip Test Research Laboratory using ITRS's roadmap, etc

It was decided the object device as a memory and SoC less than middle class. And it is clear that number of contact pads have to be reduced.



## **Target of the probe Card**

- Wafer Size : 300mm
- Probe Quantity : 150k
- Pad Size : 60µm
- Pad Pitch :  $min 90\mu m$

- Current : 5kA / wafer
- Power : 15kw / wafer
- Temperature : -40 125 deg. C

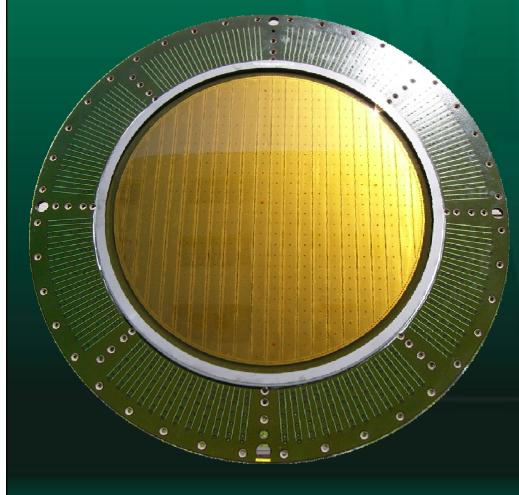


### The Issue for 150k contact on 300mm

The total load on 300mm wafer is 7,000N (700 kg) or more
Uniform pressure in the 300mm area
Stable contacts without scrub



### **150k Probe Card Over View**

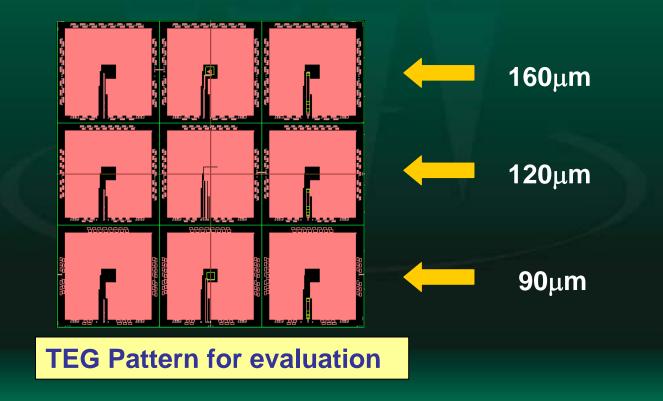


For Memory & Logic 150k Bumps Min. Pitch 90µm Membrane with Bumps Pressurization using atmosphere



## **150k Probe Card Detail**

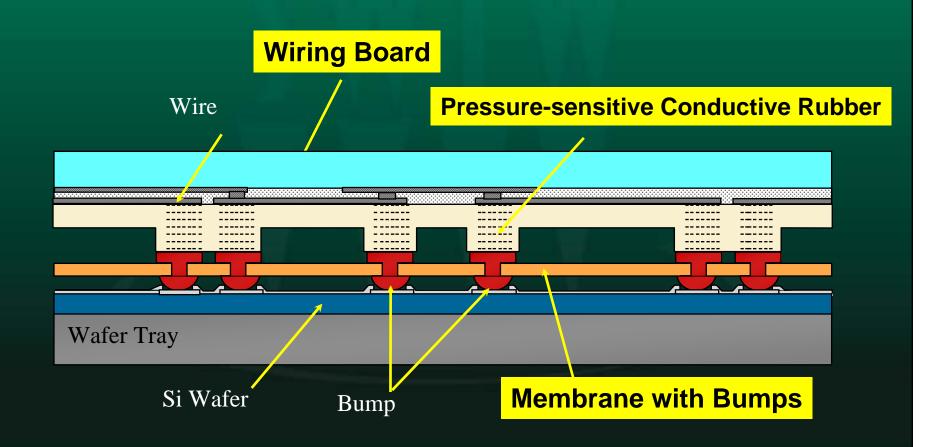
Pad Pitch	160µm	<b>120</b> µm	90µm	Total
Bumps	49,147	51,322	50,114	150,583





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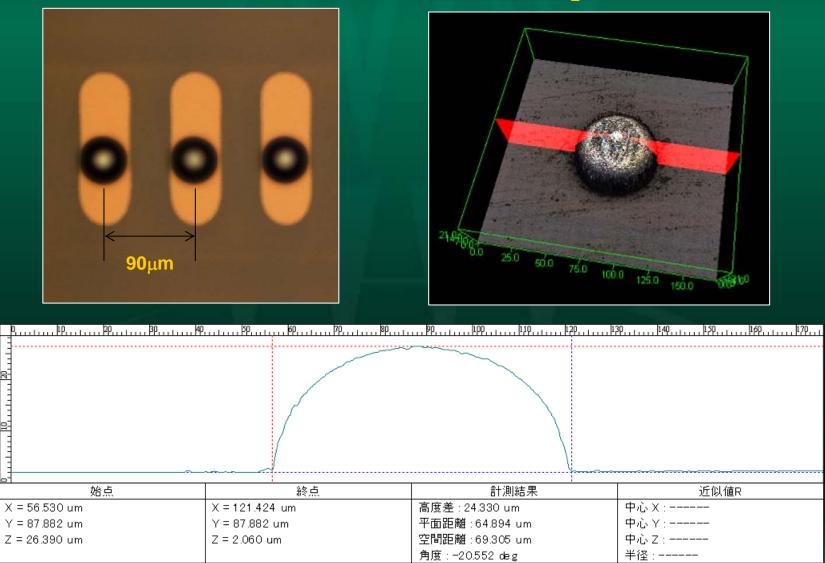
## **Detailed Structure of Probe**

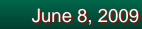




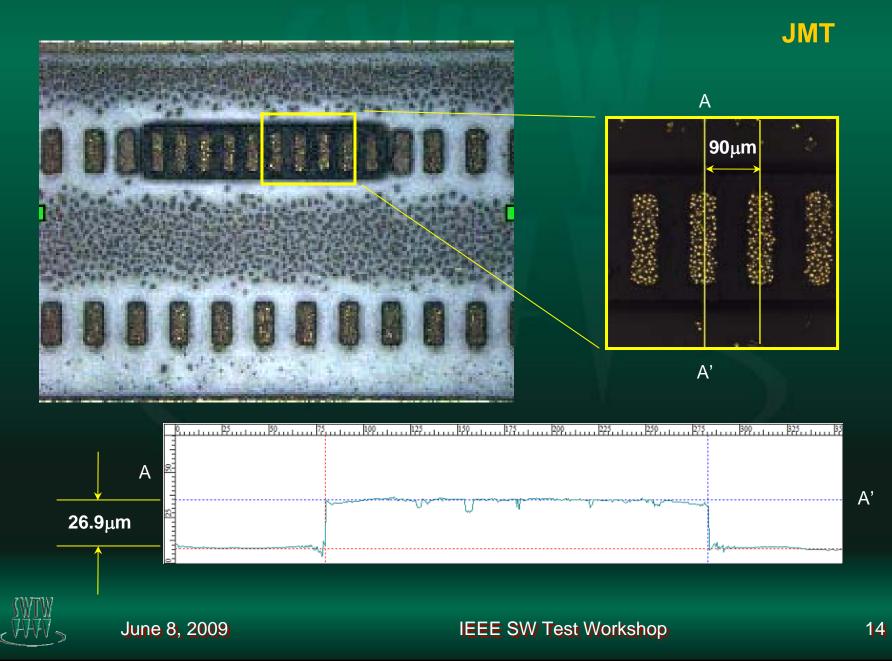
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### **Contact Bump**





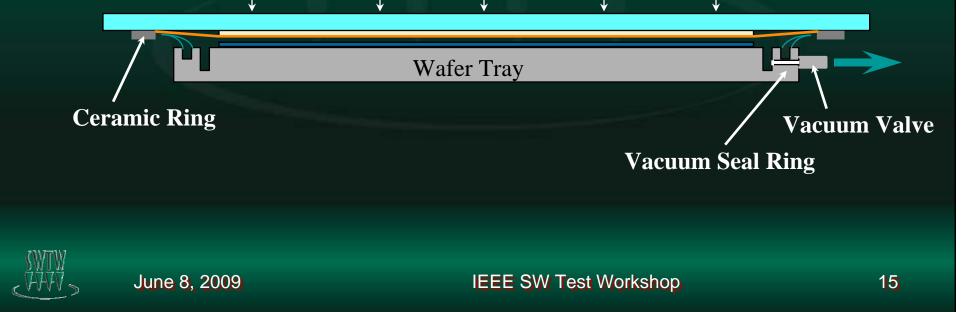
### **Pressure-sensitive Conductive Rubber**



### **Atmospheric Pressure**

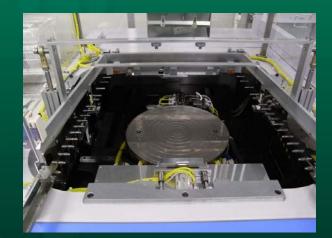
### Total load : 15.3[cm] <sup>2</sup> x $\pi$ x 97[kPa] = 7,129 [N]





### **Alignment Station**





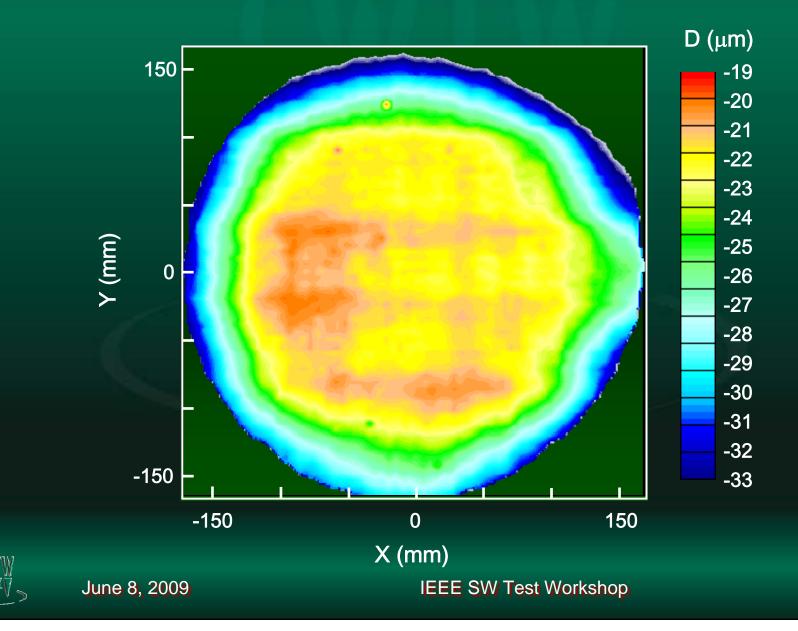
Base Machine : TSK UF300 Max. z-load : 100kg

### **Alignment Station by TSK**

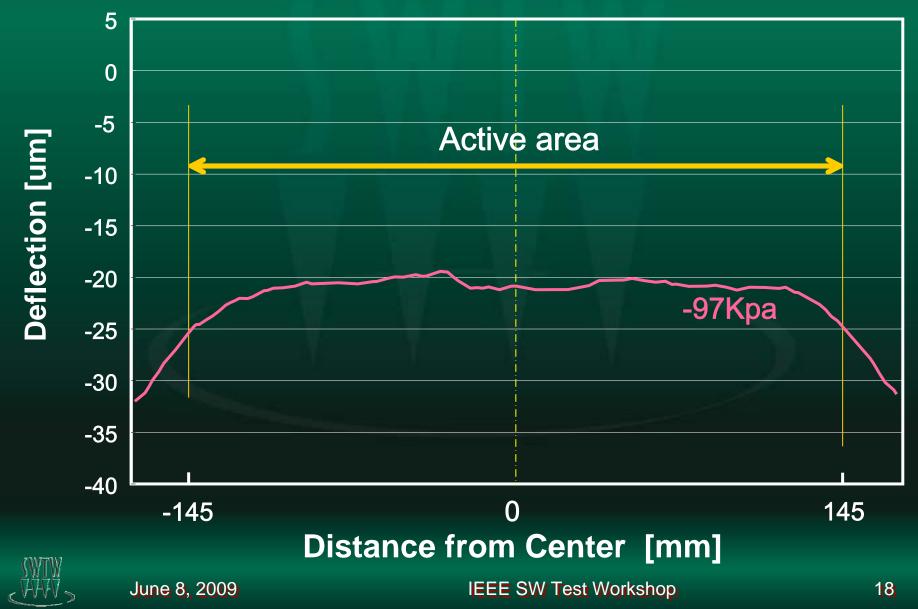


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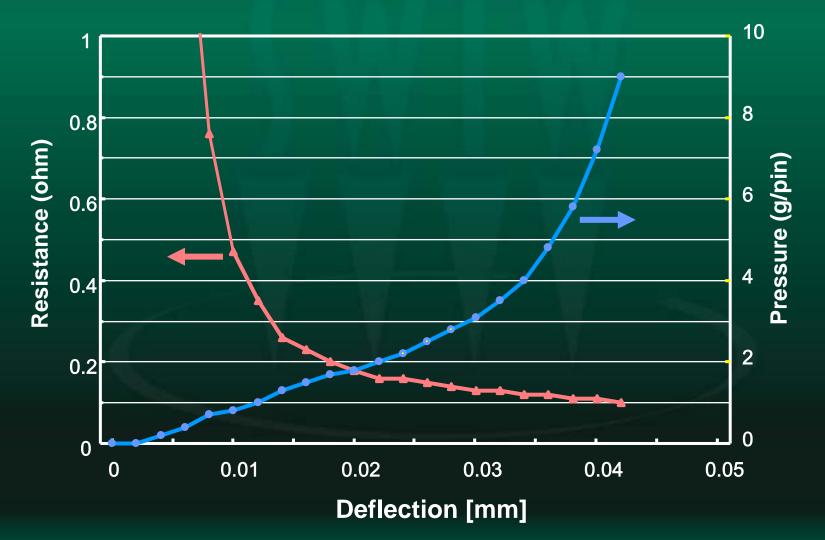
### **PCB Bend Characteristic**



### **PCB Deflection**



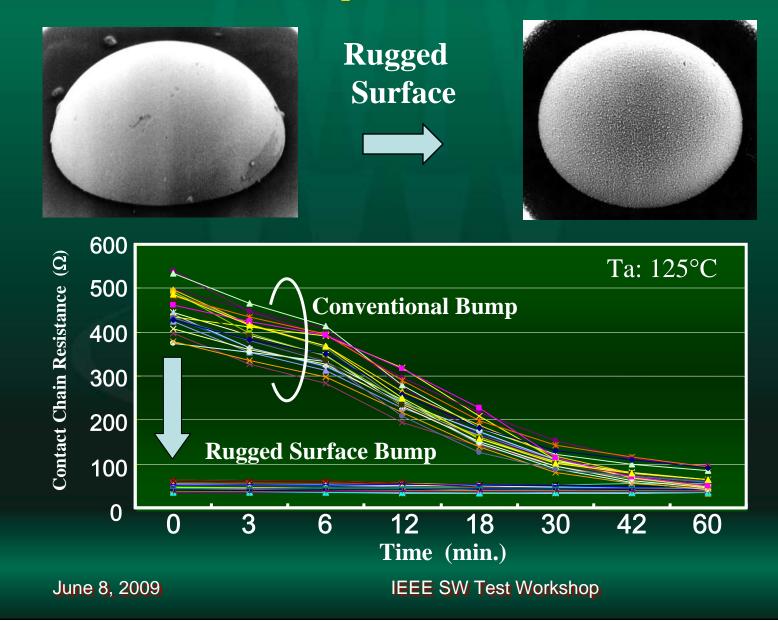
### **PCR Characteristic**





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### **Bump surface**



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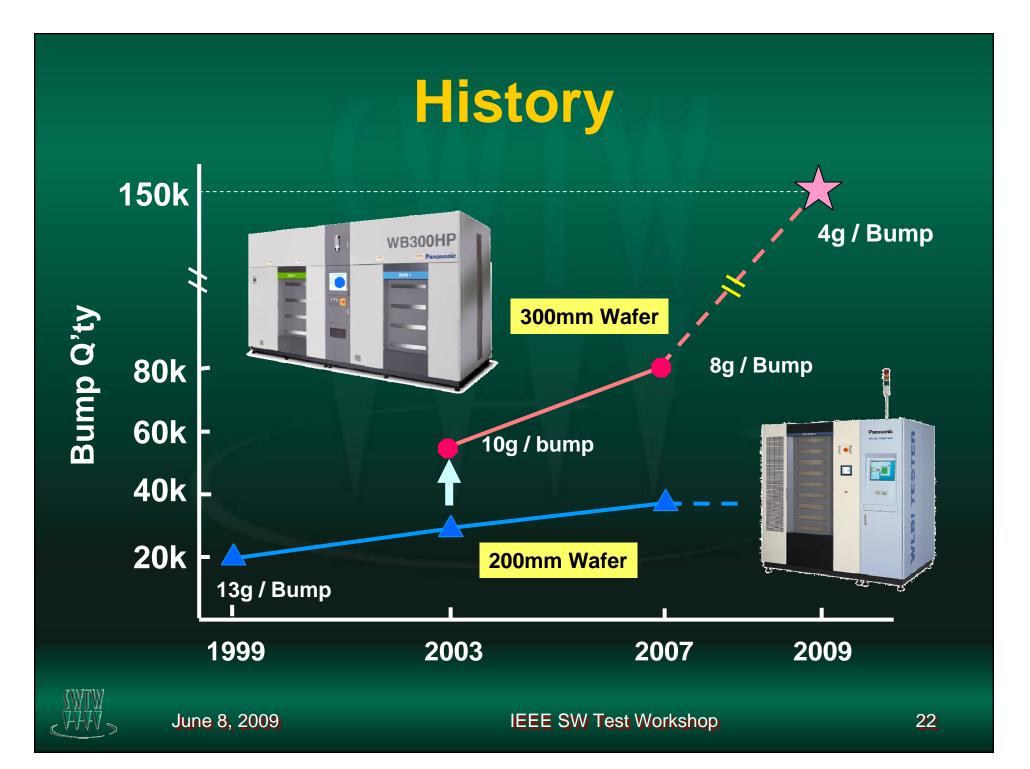
## **150k Contact Results**

Pad Pitch	<b>160</b> μ <b>m</b>	<b>120</b> μm	90µm	Total w/o dummy
Bumps*	49,147	51,322	50,114	150,583
Load [ mN ] / Bumps	39	39	39	
Load [ N ] / Wafer				5,850
Result	Bump contact + PCR +Circuit = 100 ~ 200 [mΩ]/ pin			0

\* Count out Dummy Bumps of out side



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# Summary

- Stable contacts have been achieved by 150k bumps.
- The total load on 300mm wafer is 7,000N or more, which is achieved by using a uniform atmospheric pressure method.
- Probe card does not need special structure (e.g. stiffener) nor special alignment system.

This leads to a realization of a cost effective and new concept test system.



## **Acknowledgements**

### Special Thanks to :

HOYA : Mr. Sugihara, Mr. Tsukino, Mr. Sawada
JSR : Mr. Harada, Mr. Satoh, Mr. Mayumi
TSK : Mr. Ishimoto, Mr. Watanabe
Panasonic : Mr. Miyake
ASET : Mr. Inagaki, Mr. Kada, and All of Chip Test Technology Lab.

members

This work was developed based on the WLBI technology of Panasonic.



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